

ABSTRACT

A lithographic process is disclosed. In the process, devices are fabricated by a sequence of steps in which materials are deposited on a substrate and patterned. These patterned layers are used to form devices, such as semiconductor devices, optical devices and the like over the

5 substrate. The desired pattern is formed by introducing an image of a first pattern in a layer of energy sensitive material. The image is then developed to form a pattern with features having a first size. Subsequently, the pattern is exposed to an isotropic liquid etchant to reduce the size of the features to a second, smaller size. The pattern having the features of the second, smaller size is then transferred into the underlying substrate or a layer of material formed over the substrate.